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Growth and Characterization of Bi doped Cu₂S Nano Crystalline thin films

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Abstract. Nano crystalline copper sulphide (Cu₂S) thin films pure and 3% Bi doped were deposited on glass substrate by thermal evaporation technique of thickness 400±20 nm under a vacuum of $\sim 2 \times 10^{-5}$ mbar to study the influence of annealing temperatures (as-deposited, and 573) K on structural, surface morphology and optical properties of (Cu₂S and Cu₂S:3%Bi). (XRD) X-ray diffraction analysis showed (Cu₂S and Cu₂S:3%Bi) films before and after annealing are polycrystalline and hexagonal structure. AFM measurement approves that (Cu₂S and Cu₂S:3%Bi) films were Nano crystalline with grain size of (105.05-158.12) nm. The optical properties exhibits good optical absorption for Cu₂S:3%Bi films. Decreased of optical band gap from 2.25 to 2 eV after doping which indicate good films for Photovoltaic application. The optical constants was carried out by range (300-1100) nm wave length.

Keywords: thin films, copper sulphide, Cu₂S:3%Bi, thermal evaporation.

INTRODUCTION

Because of their structural, optical, and electrical properties of Cu₂S thin films, copper sulphide is regarded as a promising material for solar energy conversion systems, particularly as p-type semiconductors [1 B]. Cu₂S thin film research has received a lot of attention in recent years because of its potential in a photovoltaic cell and its numerous technological applications in the achievement of solar cells, tubular solar cells, photovoltaic misdirection's of solar energy [2-9], vehicle glazing, as solar absorption coating, dye-sensitized solar cells, photo analyzer, microwave protective coating coatings, and sensors, and so on. [10-13]. Responsive resonator sputtering [14], alchemy bath precipitation [1,15-18], drizzle thermal decomposition [19], sequential ionic tier adsorption and response [20], microwave support chemical bath deposition [21], thermal evaporation [9], and chemical steam precipitation [22] have all been used to deposit thin films copper sulphide. Thermic vaporization was used to create thin films copper sulfide, and the impact of 3 % Bi doping and then annealing at 573 K on structure and visible characteristics was studied.

EXPERIMENTAL DETAILS

(Cu₂S) alloy was created by combining high purity (99.99 percent) copper (Cu) and sulfur (S) elements in a 1:1 atomic weight ratio, then placing it in an evacuated quartz tube that was heated at 1273 K in a thermal furnace for five hours before being allowed to cool to R.T. The tube was removed from the furnace and broken at one end to retrieve the composite ingot, which was then processed in a special mill (laboratory mill) to produce the material's powder. Cu₂S thin films were made from powder on glass substrates with R.T of 400 nm thicknesses using a thermal evaporation process in a vacuum of 10⁻⁵ mbar, then doped with 3% Bi and heat treated for an hour at 573 K. X-ray diffraction was used to study the structures of Cu₂S alloy and all films, both pure and doped, using a (SHIMADZU-Japan-XRD

6000) diffract meter system with CuK radiation. ($\lambda = 1.5418$), 20 mA current, 40Kv voltage, and optical measurements have all been performed.

RESULTS AND DISCUSSIONS

X-ray Diffraction Analyses

Figure (1) shows the XRD spectrum of Cu_2S thin films formed by thermal evaporation process with a thickness of 400 nm that are pure and doped 3 % Bi at (R.T and $T_a=573$ K). All of these XRD patterns demonstrate the polycrystalline nature of the films and the creation of the Cu_2S phase, which is archived in the standard ICDD (00-053-0522) card with peaks at $2\theta = 16.027, 36.33, 45.99, 51.82,$ and 54.40 matching to (100), (210), (220), (310), and (311) respectively. XRD patterns further demonstrate that all films made have a single phase crystal and are extremely pure, as no secondary phase is found. Furthermore, after doping and annealing (at $T_a=573$ K), the preferred orientation along the (220) plane increased, peaks were sharper, and crystalline size increased, implying that Nano crystallite size grew.

The size of the crystals is computed using Scherer's formula.[23]:

$$C.S = \frac{0.94\lambda}{\beta \cos\theta} \dots\dots\dots(1)$$

The XRD wave length is represented by: λ , The FWHM of the peaks is shown by: β , and Bragg's angle is represented by: θ , To compute the dislocation density (δ), Williamson and Smallman's equation was used [23]:

$$\delta = \frac{1}{(C.S)^2} \dots\dots\dots(2)$$

Tables (1) and (2), respectively, include all of these values for Cu_2S alloy and films.

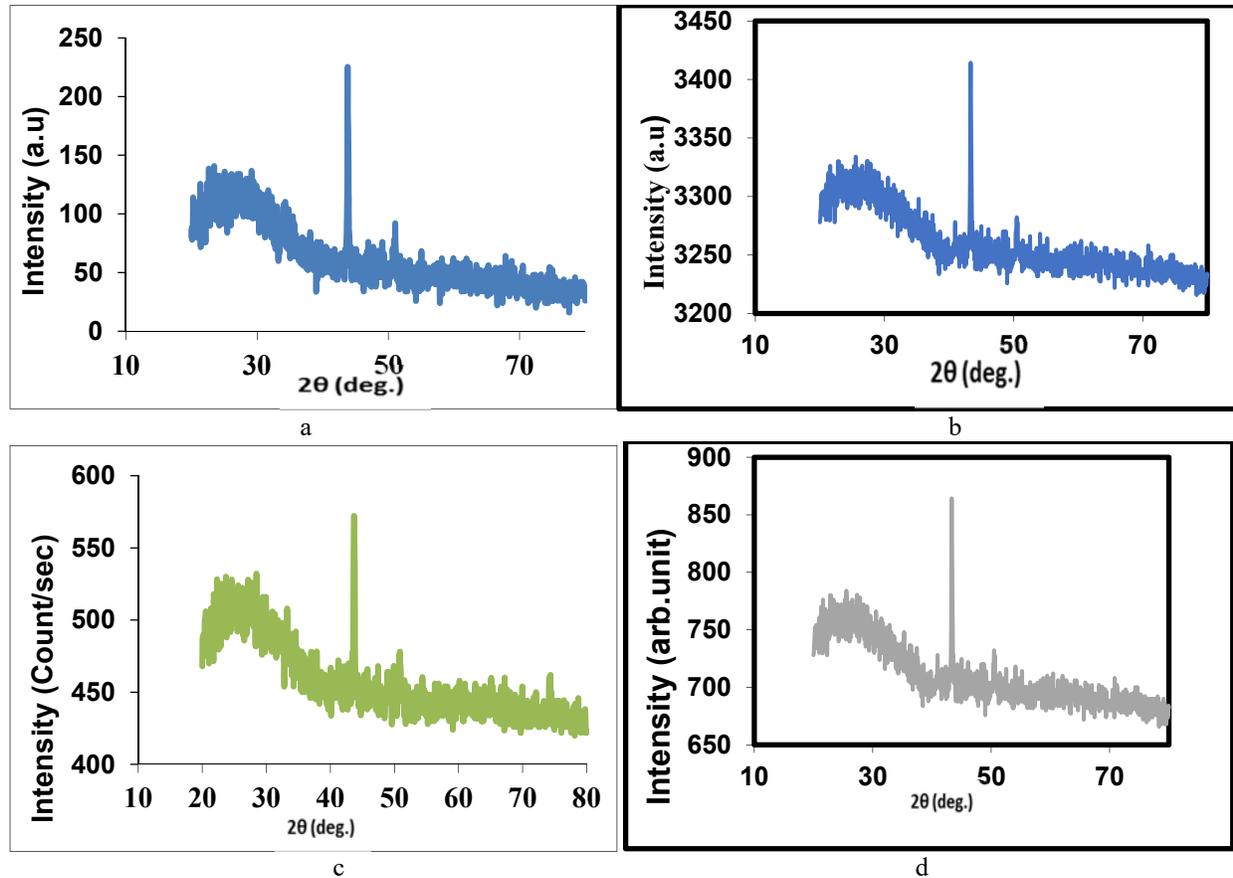


FIGURE 1. XRD results for Cu_2S thin films a) pure at R.T. b) pure at $T_a=573$ K c) 3 % Bi doped at (273k) d) 3 % Bi doped at ($T_a=573$ K)

TABLE 1. Cu₂S alloy structural characteristics.

2θ (Std.) (Deg.)	2θ (Exp.) (Deg.)	d(Std) (Å)	d(Exp) (Å)	hkl	FWHM (Deg.)	C.S (nm)	a(Std.) (Å)	a(Exp.) (Å)
15.9152	16.0272	5.564000	5.52550	100				
36.1076	36.3375	2.485500	2.47036	210				
46.1034	45.9980	1.967200	1.97151	220	0.39570	22.7998	5.564Å	5.570Å
51.9251	51.8274	1.759500	1.76263	310				
54.6724	54.4014	1.677400	1.68516	311				

TABLE 2. Characteristics of Cu₂S films structure.

Sample	T(K)	2θ	FWHM(deg)	d _{hkl} (exp) A°	d _{hkl} (std) A°	C.S (nm)	δ* 10 ¹⁵ (lines/m ²)
Cu ₂ S	R.T	43.8375	0.21220	2.0723	2.0635	42.1583	0.000562
		51.0178	0.30000	1.7900	1.7886	30.659	0.00107
Cu ₂ S	573	35.5424	0.5900	2.5257	2.5237	14.7747	0.00458
		38.7098	0.7000	2.3260	2.3242	12.5697	0.006329
Cu ₂ S:3% Bi	573	36.3733	0.29820	2.4679	2.46801	9.96642	0.010067
		35.5174	0.34000	2.25409	2.52550	25.6458	0.001520

(AFM) Measurement

Surface morphology of Cu₂S films pure and doped %3 Bi were analyzed using AFM at (R.T and Ta=573 K). Figure 2 shows AFM images of Cu₂S films in three dimensions (3D). These pictures indicate that all films are packed together and distributed in a uniform manner, with no pinholes or cracks. Table (3) shows AFM data; from this table, it can be determined that average grain size increased from (105.05) nm to (158.12) nm. After doping and annealing (at Ta=573 K), the toughness of film surfaces increased, and the root-mean square RMS surface changed due to structural enhancement, which agrees with X-ray diffraction results.

TABLE 3. Cu₂S thin film AFM results

Thin Films	T _a (K)	Surfaces roughness (nm)	Root mean Sq.(nm)	Grain Size(nm)
Pure	R.T	5.93	7.16	105.05
	573	23.8	29.5	170.82
Cu ₂ S :3%Bi	R.T	4.16	5.18	158.12
	573	2.39	3.21	144.18

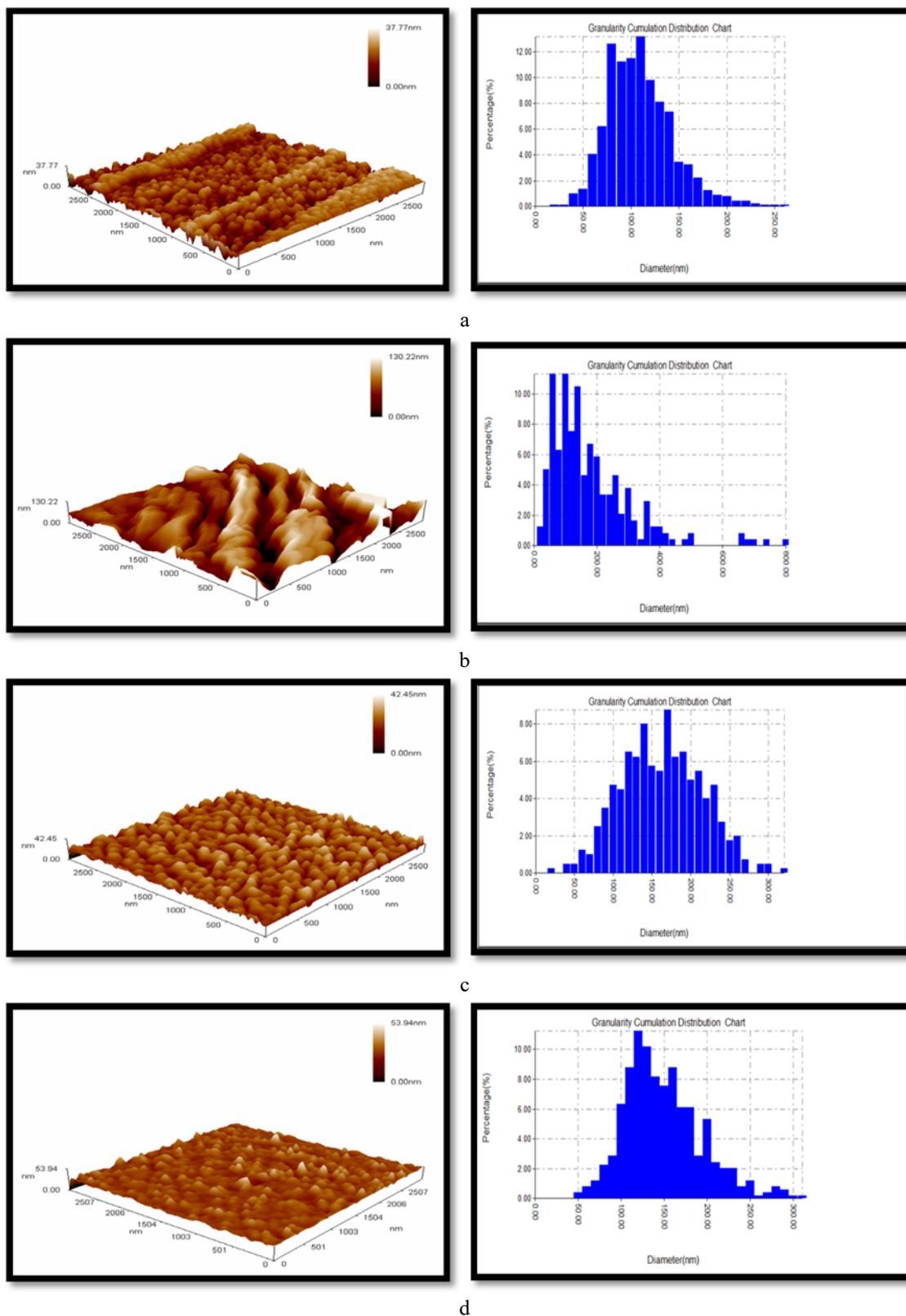


FIGURE 2. AFM images of Cu_2S thin films. a) pure at R.T. b) pure at $T_a=573$ K. c) doped 3% Bi at (273k). d) doped 3%Bi at ($T_a=573$ K)

Optical Measurement

Figure 3 depicts the absorbance (A) as a function of wavelength limited extent (300 – 1000) nm for Cu₂S thin films pure and doped 3% Bi at (R.T and Ta=573 K) . This form shows how absorption values increase after doping and annealing due to a reduced cereal border and the creation of microscopic cereal, but decrease as wave length increases. Cu₂S films have a high absorption value across a wide wavelength range (400-600 nm), making them suitable for solar cell implementation. At (R.T and Ta=573 K), the permeability (T) of Cu₂S thin films pure and doped with % Bi is shown in Figure (4). The value of permeable increases with increasing wave length and high values in the NIR area, and increases after doping and annealing, this behavior relating to differences in crystal structure after doping and annealing is obvious from this form. As demonstrated in form (5)., all Cu₂S films have substantial absorption coefficients ($\alpha > 10^4 \text{ cm}^{-1}$). This suggests that a direct transfer is likely to be permitted. In addition, the values of the absorption coefficient increase after doping, but the absorption coefficient is slightly reduced after annealing, resulting in a lower energy displacement, because absorption is not solely the responsibility of the freedom holders, but also of impurities or electronic states in a steady state.

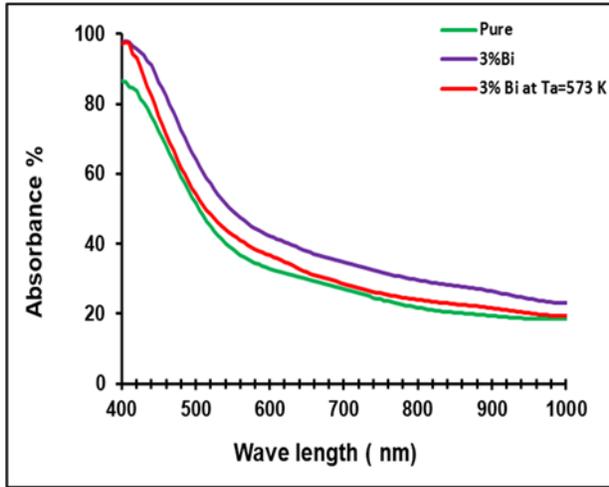


FIGURE 3. Cu₂S thin film absorption as of wavelength.

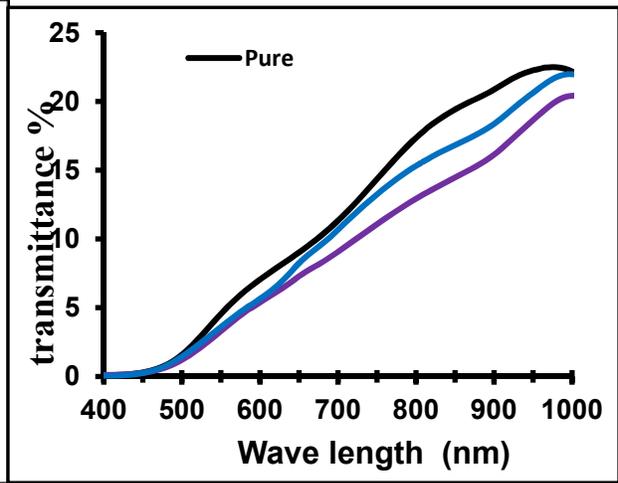


FIGURE 4. The permeability of Cu₂S thin films as a function of a wavelengths.

The visual energy gap (E_g^{opt}) values determined from Tauc's equation are plotted $(\alpha h\nu)^2$ as a function of photon energy ($h\nu$) in Figure (6) :[24,25]

$$(\alpha h\nu) = A(h\nu - E_g)^n \quad \dots\dots\dots(3)$$

Where A: is constant and n is a variable number based on the type of visual transition. After doping, the visible energy gap values of Cu₂S thin films decreased from (2.25eV) to (2eV), but after annealing, the energy gap value increased to (2.2eV), indicating a red shift towards the absorption edge, as illustrated in Figures (6) and (7). Due to the difference in ionic radii, this behavior can be attributed to an increase in defects as a result of combining Cu⁺² ions with Bi⁺³ ions. These values produce good material for solar cells.

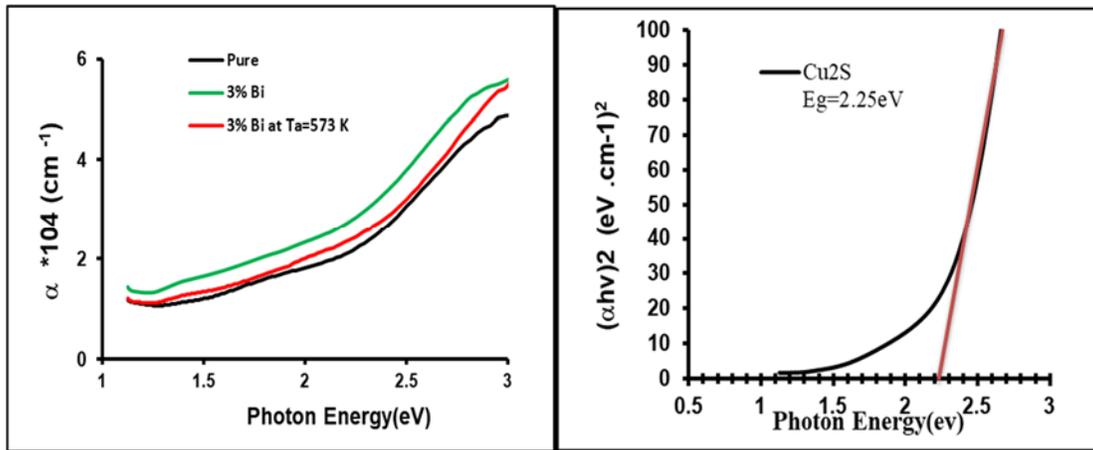


Figure 5. The relation between the absorption coefficient and photon (a) energy for Cu₂S thin films.

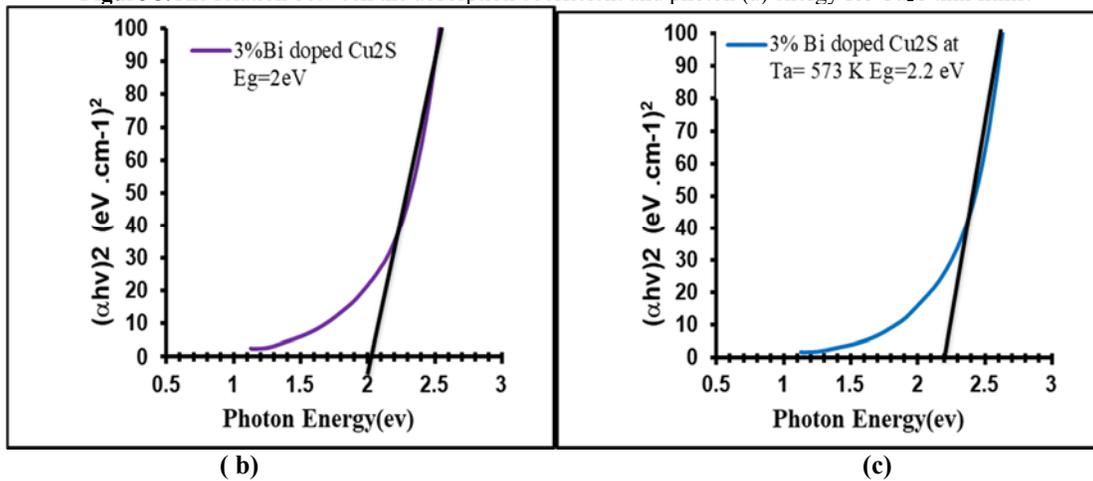


FIGURE 6. In Cu₂S thin films, the connection between $(\alpha h\nu)^2$ and photon energy. a) pure at R.T. b) 3 % Bi (Cu₂S) doped at R.T , b) 3% Bi doped at (Ta=573 K) .

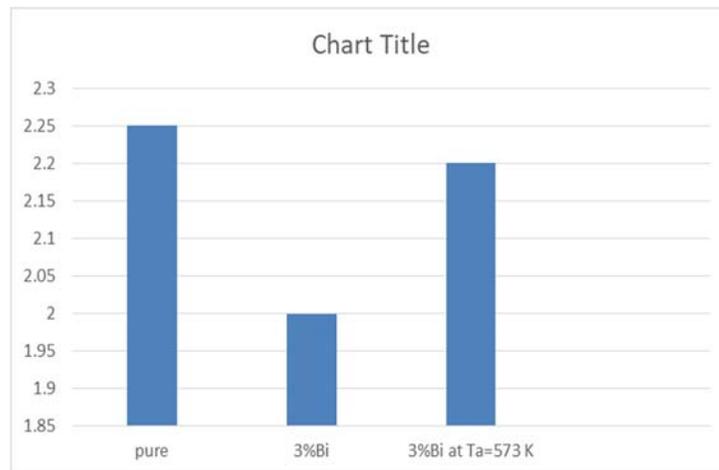


FIGURE 7. The optical energy gap for (Cu₂S and Cu₂S:3% Bi) films.

The formula can be used to compute refractive index values: [26]

$$n = \{ [4R / (R-1)] - K^2 \}^{1/2} - [(R+1) / (R-1)] \dots \dots \dots (4)$$

R is the reflectance, which is computed using the following equation:

$$R = 1 - T - A \dots\dots\dots (5)$$

The absorption coefficient (α) and the extinction coefficient (K) are connected by: [27]

$$\alpha = 4\pi K / \lambda \dots\dots\dots (6)$$

Figure 8 shows the behavior of the refractive index (n) with photon energy for (Cu₂S, Cu₂S:3 % Bi, and Cu₂S:3 % Bi at Ta=573 K) films. At increasing photon energy, refractive index values increase due to changes in the structural properties of films after doping and annealing. Figure (9) shows the fluctuation of the extinction coefficient (K) with photon energy for pure and doped % Bi Cu₂S thin films at (R.T and Ta=573 K), We can see from this graph that the extinction coefficient values increase after doping and annealing, and that this behavior is comparable to that of the absorption coefficients across the whole wavelength spectrum.

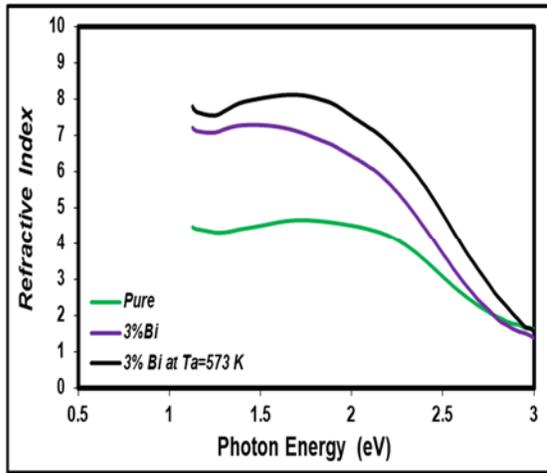


FIGURE 8. Variation of refractive index versus photon energy in Cu₂S thin films.

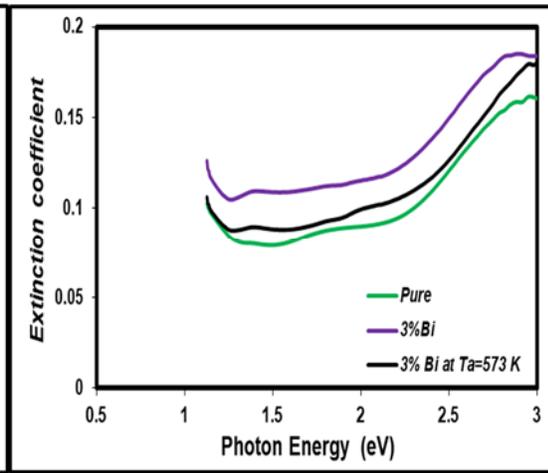


FIGURE 9. Extinction coefficient difference as a function of photon energy in Cu₂S thin films.

The real and imaginary parts of the dielectric constant (ϵ_1 , ϵ_2) can be computed using the equation: [26].

$$\epsilon_1 = n^2 - K^2 \dots\dots\dots (7)$$

$$\epsilon_2 = 2nK \dots\dots\dots (8)$$

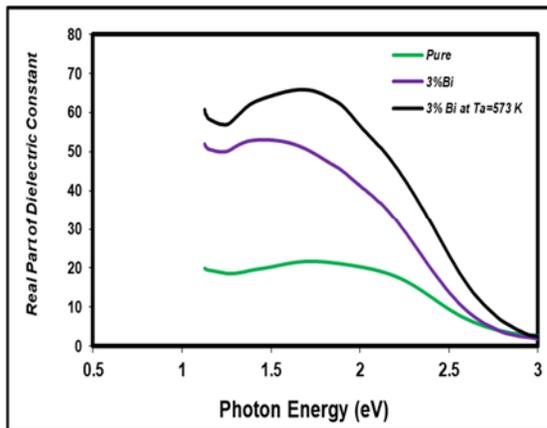


Figure 10 shows the difference of the real part of the dielectric constant versus photon energy in Cu₂S thin films.

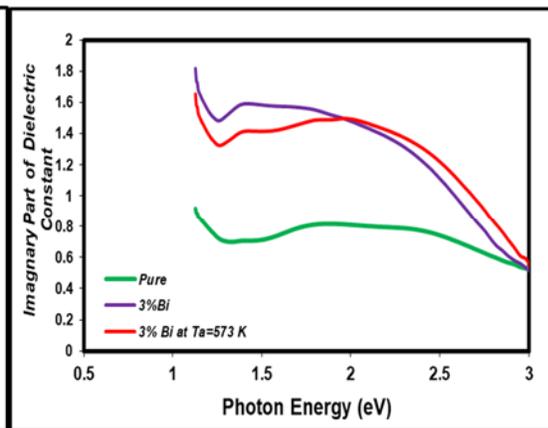


Figure 11 shows the difference of the imaginary part of the dielectric constant versus photon energy in Cu₂S thin films

The fluctuation of the real (ϵ_1) and imaginary (ϵ_2) components of the dielectric constant values vs photon energy for (Cu₂S, Cu₂S:3% Bi, and Cu₂S:3% Bi at Ta=573 K) films is shown in Figures 10 and 11. The refractive index numbers determine the real component of the dielectric constant, whereas the extinction coefficient values determine the imaginary part of the dielectric constant.

CONCLUSION

XRD results show that the films were formed of Cu₂S phase and polycrystalline with preferential orientation in (220) direction in this study, which determines the influence of doping (3% Bi) and annealing temperatures on structural. Surface morphology and optical characteristics of Cu₂S thin films with a thickness of 400nm successfully produced on a glass substrate using the thermal evaporation process at R.T. The AFM results demonstrate that following 3% Bi doping and annealing temperature, both grain size and surface roughness altered. Increase grain size from 105.05 to 158.12 nm due to structure improvement and Low roughness can get good character for photovoltaic cell properties. Cu₂S films band gap energy values are depending on doping and annealing, decrease from 2.25 to 2 eV, lower values are obtained for Cu₂S:3% Bi with low transmittance. Films' optical properties indicate that they are suitable for photovoltaic applications.

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